The present invention provides a particle-measuring system mounted on a processing system that has a processing unit for carrying out a predetermined processing of an object to be processed and an exhaust system for exhausting an atmospheric gas from within a processing chamber of the processing unit by a vacuum pump. Within the processing system, the particle-measuring system is installed on an exhaust pipe that forms a part of the exhaust system communicating between an exhaust opening of the processing chamber and the vacuum pump. With this arrangement, the particle measuring system measures the number of the particles included in the exhaust gas discharged from within the processing chamber.

Please replace the paragraph beginning on page 17, line 23, with the following text:

As a processing gas from a processing gas source (not shown), gases of WF_6 (a raw material gas), SiH_2Cl_2, Ar, etc. are supplied by a predetermined volume for each gas to the shower head 72, and the gases are mixed together to from the processing gas. The processing gas is then supplied approximately uniformly to within the processing chamber 48 from the gas injection holes 78.

Please replace the paragraph beginning on page 19, line 21, with the following text:

The laser beams L may be irradiated in any direction so long as the irradiated laser beams L are directed to the direction in which the center axis 92 of the chamber exists through the center point O of the cross section. However, a relative positional relationship with the scattered light detector 106 is maintained.

Please replace the paragraph beginning on page 32, line 20, with the following text:

In the above description, a film-forming system has been explained by taking a lamp-heating system as an example. However, the film-forming system is not limited to this. It needs not be mentioned that the present invention can also be applied to a resistor-heating